Supplementary Information:

## A Self-Driven Wideband Wavelength Sensor Based on an Individual

## PdTe<sub>2</sub>/Thin Si/PdTe<sub>2</sub> Heterojunction

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Figure S1. Schematic diagram of the procedures for synthesizing 2D  $PdTe_2$  nanofilm and fabricating the designed color sensor.



Figure S2. SEM images of the 2D PdTe2 synthesized at different temperatures of (a) 563 K, (b) 583 K and (c) 673 K.



Figure S3. The corresponding EDS mapping of 2D PdTe<sub>2</sub> nanofilm on thin Si.



**Figure S4**. (a) Raman spectrum, (b) XRD pattern, (c) XPS spectrum, (d) XPS spectra of Pd 3d (left panel) and Te 3d (right panel), and (e) EDS spectrum of the as-synthesized PdTe<sub>2</sub> nanofilm.



Figure S5. The noise spectral density of the PdTe<sub>2</sub>/thin Si/PdTe<sub>2</sub> heterojunction.



**Figure S6**. Transient photoresponse of the  $PdTe_2/Si/PdTe_2$  heterojunction device (a) at light modulation frequency of 12 kHz, (b) under 730 nm light illumination over 8000 cycles of operation, and (c) before and after storage in ambient conditions for 3 months.



Figure S7. Optical absorption spectra of Si wafers with diverse thicknesses.



**Figure S8**. (a) Photocurrents at front- and back-illuminated modes and (b) photocurrent ratio *versus* light wavelength of 100  $\mu$ m-thick Si device at light intensity of 60  $\mu$ W cm<sup>-2</sup>.

Light intensity	Bias voltage	Α	В	С	D
50 μW cm <sup>-2</sup>	0 V	60.43389	104.0626	2.54829	370.8137
30 µW cm <sup>-2</sup>	0 V	73.62578	114.8314	2.13944	362.4086
20 μW cm <sup>-2</sup>	0 V	72.76912	112.8695	2.22853	371.5909
10 μW cm <sup>-2</sup>	0 V	76.66907	120.7684	2.00986	376.5797
10 μW cm <sup>-2</sup>	-0.1 V	82.0998	130.6842	1.61825	348.5703
10 μW cm <sup>-2</sup>	-0.2 V	81.80273	126.3258	1.54657	349.9691
10 µW cm <sup>-2</sup>	-0.3 V	81.22581	123.8618	1.59006	348.3812

**Table S1.** The values of the constants of the work curve at several specific light intensities and working bias voltages.